Speaker of Session 25

ATOMIC LAYER DEPOSITION TECHNOLOGY

Leo D. Salmi received his MSc in inorganic chemistry from the University of Helsinki, Finland in 2007. His master's thesis work concerned synthesizing a new precursor for atomic layer deposition (ALD) of erbium oxide thin films and characterization of the deposition process.

Currently Leo is finishing his PhD studies under the supervision of Prof. Mikko Ritala in the thin film group of the Laboratory of Inorganic Chemistry at the University of Helsinki. His work involves ALD of inorganic-organic hybrid thin films including the development and characterization of new materials and processes.

Publications in Refereed Journals

Studies on Atomic Layer Deposition of IRMOF-8 Thin Films
Salmi, L. D., Heikkilä, M., Vehkamäki, M., Puukilainen, E., Sajavaara, T. P. & Ritala, M. (2015) *Journal of Vacuum Science & Technology A*. 33, 1, 01A121-1 - 01A121-8.

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